

<b>Notice of References Cited</b>	Application/Control No. 10/743,985		Applicant(s)/Patent Under Reexamination CHENG ET AL.	
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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Y.C. King et al., "Sub-5um Multiple Thickness Gate Oxide Technology Using Oxygen Implantation," Int. Electron Device Meeting (IEDM), San Francisco, paper 21.1.1, 1998).
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